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APPLICATION NO.	FILI	ING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/684,794	10/14/2003		Jeffrey L. Mackey	108298740US	4238	
25096	7590	09/21/2004		EXAMINER		
PERKINS C	OIE LLP		NGUYEN	NGUYEN, HUNG		
PATENT-SEA	Ą					
P.O. BOX 124	47		ART UNIT	PAPER NUMBER		
SEATTLE, V	VA 9811	1-1247	2851			
				DATE MAIL ED. 00/21/200	DATE MAILED, 00/21/2004	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)				
		10/684,794	MACKEY ET AL.				
Office Action Summary		Examiner	Art Unit				
		Hung Henry V Nguyen	2851				
	The MAILING DATE of this communication a		with the correspondence add	dress			
Period fo	•						
THE - External after - If the - If NC - Failu Any	ORTENED STATUTORY PERIOD FOR REP MAILING DATE OF THIS COMMUNICATION nsions of time may be available under the provisions of 37 CFR SIX (6) MONTHS from the mailing date of this communication. period for reply specified above is less than thirty (30) days, a reperiod for reply is specified above, the maximum statutory period for reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply within the set or extended period for reply will, by statication reply will, by statication reply within the set or extended period for reply will, by statication reply will, by statication reply within the set or extended period for reply will, by statication r	I. 1.136(a). In no event, however, may a eply within the statutory minimum of th d will apply and will expire SIX (6) MC tte, cause the application to become	a reply be timely filed airty (30) days will be considered timely DNTHS from the mailing date of this co ABANDONED (35 U.S.C. § 133).				
Status							
1)[\inf	Responsive to communication(s) filed on 14	October 2003.					
·		is action is non-final.					
3)							
	closed in accordance with the practice under Ex parte Quayle, 1935 C.D. 11, 453 O.G. 213.						
Dispositi	on of Claims						
4)⊠	Claim(s) 1-49 is/are pending in the application	on.					
-	4a) Of the above claim(s) is/are withdrawn from consideration.						
5)⊠	∑ Claim(s) <u>27-29, 48 and 49</u> is/are allowed.						
6)⊠	⊠ Claim(s) <u>1,2,5,9-13,16-18,30,31,33,34,37-41 and 43-45</u> is/are rejected.						
7)🖂	☑ Claim(s) <u>3,4,6-8,14,15,19-26,32,35,36,42,46 and 47</u> is/are objected to.						
8)	Claim(s) are subject to restriction and	or election requirement.					
Applicati	on Papers						
9)[The specification is objected to by the Exami	ner.					
10)🖂	10)⊠ The drawing(s) filed on <u>14 October 2003</u> is/are: a)⊠ accepted or b)□ objected to by the Examiner.						
	Applicant may not request that any objection to the	e drawing(s) be held in abeya	ance. See 37 CFR 1.85(a).				
	Replacement drawing sheet(s) including the correction is required if the drawing(s) is objected to. See 37 CFR 1.121(d).						
11)	The oath or declaration is objected to by the	Examiner. Note the attache	ed Office Action or form PT	O-152.			
Priority ι	ınder 35 U.S.C. § 119	, i					
12)	Acknowledgment is made of a claim for foreig	n priority under 35 U.S.C.	§ 119(a)-(d) or (f).				
a)	☐ All b)☐ Some * c)☐ None of:						
	1. Certified copies of the priority docume	nts have been received.					
	2. Certified copies of the priority docume		· · · · · · · · · · · · · · · · · · ·				
	3. Copies of the certified copies of the pr		n received in this National	Stage			
	application from the International Bure	, , , , , , , , , , , , , , , , , , , ,					
* 5	See the attached detailed Office action for a li	st of the certified copies no	it received.				
Attachmen							
	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948)		Summary (PTO-413) o(s)/Mail Date				
3) 🛛 Infor	mation Disclosure Statement(s) (PTO-1449 or PTO/SB/0	8) 5) Notice of	Informal Patent Application (PTC)-152)			
Paper No(s)/Mail Date <u>2,4/04 and 10/03</u> .							

Application/Control Number: 10/684,794

Art Unit: 2851

DETAILED ACTION

Claim Rejections - 35 USC § 102

1. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(e) the invention was described in a patent granted on an application for patent by another filed in the United States before the invention thereof by the applicant for patent, or on an international application by another who has fulfilled the requirements of paragraphs (1), (2), and (4) of section 371(c) of this title before the invention thereof by the applicant for patent.

The changes made to 35 U.S.C. 102(e) by the American Inventors Protection Act of 1999 (AIPA) and the Intellectual Property and High Technology Technical Amendments Act of 2002 do not apply when the reference is a U.S. patent resulting directly or indirectly from an international application filed before November 29, 2000. Therefore, the prior art date of the reference is determined under 35 U.S.C. 102(e) prior to the amendment by the AIPA (pre-AIPA 35 U.S.C. 102(e)).

2. Claims 1-2, 5, 9-13, 16-18, 30-31, 33-34, 37-41, and 43-45 are rejected under 35 U.S.C. 102(e) as being anticipated by Sandstrom (U.S.Pat. 6,504,644).

The applicant is reminded that the claimed subject matter to examination will be given their broadest reasonable interpretation consistent with the specification, and limitations appearing in the specification are not be read into the claims. In re Yamamoto, 740 F. 2d 1569, 1571, 222 USPO 934, 936 (Fed.Cir. 1984). With this in mind, the rejection herein will focus on how the terms and relationships thereof in the claims are met by the references. Response to any limitation that is not in the claims or any argument that is irrelevant to or does not relate to any specific claimed language will not be warranted.

Application/Control Number: 10/684,794 Page 3

Art Unit: 2851

With respect to claims 1, 10-11, 16-18, 30-31, 34, 37-41 and 43-45, Sandstrom discloses an apparatus and corresponding method for controlling characteristics of radiation directed to a microworkpiece and comprising all basic features of the instant claims such as: a workpiece support (605) having a support surface positioned to carry a microlithographic workpiece (see col.14, lines 14-17); a EUV light source positioned to direct a radiation beam along a radiation path toward the workpiece support, the radiation beam having an amplitude distribution, a phase distribution and a polarization distribution; and SML can be regarded as claimed "an adaptive structure" positioned in the radiation path between the source of radiation and the workpiece support, the SLM includes a plurality of individually addressable pixel elements, at least one of these pixel elements includes a layer of electro optical material having a birefringence that varies according to an applied voltage. Each of the plurality of pixel elements is selectively configurable to change form one state to any of a plurality of other states and to modulate both of an amplitude and a phase of radiation that is incident on the pixel element (see col.3, lines 35-67; figures 1-4) and a controller (607) operatively coupled to "the adaptive structure" to direct the elements of the adaptive structure to change from the one state to the one of the plurality of other states.

As to claims 2, Sandstrom teaches the controller (607) is electrically coupled to each of the elements and is configured to apply a variable voltage to each element to independently change a stage of each element from one state to any a plurality of available other states (see figure 1).

As to claim 3, Sandstrom teaches the elements of the adaptive structure (SLM) having a non-time varying transmissibility in each of the states.

With respect to claims 9 and 33, Sandstrom discloses the adaptive structure having a plurality of electrically addressable elements arranged in an array of column and rows (see figure 2).

Allowable Subject Matter

- 3. Claims 3-4, 6-8, 14-15, 19-26, 32, 35-36, 42, 46-47 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.
- 4. Claims 27-29, 48-49 are allowed.
- 5. The following is a statement of reasons for the indication of allowable subject matter: the prior art either alone or in combination, neither discloses nor makes obvious the combination of an apparatus and corresponding method for controlling characteristic of radiation directed to a microlithographic workpiece, comprising a reticle, an adaptive structure and a controller with particular structures and functions, as recited in the instant claims of the present invention.

Prior Art Made of Record

6. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Johnson (U.S.Pat. 6,498,685); and Shiraishi et al (U.S.Pat. 6,710,854) discloses exposure apparatuses and have been cited for technical background.

Application/Control Number: 10/684,794 Page 5

Art Unit: 2851

7. Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Hung Henry V Nguyen whose telephone number is 571-272-

2124. The examiner can normally be reached on Monday-Friday (First Friday off).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Judy Nguyen can be reached on 571-272-2258. The fax phone number for the

organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Hung Henry V Nguyen

Primary Examiner
Art Unit 2851

hvn 9/4/05